

| | Type | L # | Hits | Search Text | DBs | Time Stamp | Comments |
|---|------|-----|------|--|---|------------------|----------|
| 3 | BRS | L3 | 212 | ((Ge or germanium or Ge?sub\$4) near15 (Se or selenium or Se?sub\$4)) or (GeSe or SeGe)) same (resist or photoresist or photoresin or photosensitive or (photo adj (resist or active or sensitive))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM-TDB- | 2004/07/21 11:33 | |
| 4 | BRS | L5 | 54 | 3 and ((remov\$4 or etch\$4 or ash\$4 or clean\$4) with (O2 or oxygen or "O?sub. 2" or O?sub\$2 or dry or RIE)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM-TDB- | 2004/07/21 11:51 | |

| | Type | L # | Hits | Search Text | DBs | Time Stamp | Comments |
|---|------|-----|------|---|--|------------------|----------|
| 1 | BRS | L1 | 210 | ((Ge or germanium or Ge?sub\$4) near15 (Se or selenium or Se?sub\$4)) or (GeSe or SeGe)) same (resist or photoresist or photoresin or photosensitive or (photo adj (resist or active or sensitive)) same (mask\$4 or photomask\$4)) | USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM- TDB | 2004/07/21 10:31 | |
| 2 | BRS | L2 | 23 | 1 same (Plasma or oxymen or O2 or "O.sub. 2" or O?sub\$2) | USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM- TDB | 2004/07/21 10:32 | |